

EXHIBIT D

IN THE UNITED STATES DISTRICT COURT
FOR THE WESTERN DISTRICT OF TEXAS
WACO DIVISION

DEMARAY LLC,
Plaintiff

-v-

INTEL CORPORATION,
Defendant

W-20-CV-00634-ADA

DEMARAY LLC,
Plaintiff

-v-

SAMSUNG ELECTRONICS CO., LTD.
(A KOREAN COMPANY), SAMSUNG
ELECTRONICS AMERICA, INC.,
SAMSUNG SEMICONDUCTOR, INC.,
SAMSUNG AUSTIN
SEMICONDUCTOR, LLC,
Defendants

W-20-CV-00636-ADA

CLAIM CONSTRUCTION ORDER

The Court held a supplemental *Markman* hearing on February 28, 2022. During that hearing, the Court provided its final constructions. The Court now enters those claim constructions.

SIGNED this 28th day of February, 2022.


ALAN D ALBRIGHT
UNITED STATES DISTRICT JUDGE

Term	Plaintiff's Proposed Construction	Defendants' Proposed Construction	Court's Final Construction
<p data-bbox="201 277 590 383">“A method of depositing an insulating film on a substrate, comprising:”</p> <p data-bbox="201 423 548 488">U.S. Patent No. 7,381,657, Claim 2</p>	<p data-bbox="630 277 1037 383">Preamble is not limiting, except for “insulating film on a substrate”</p>	<p data-bbox="1058 277 1465 383">Preamble is limiting (“<i>depositing an</i> insulating film on a substrate”)</p>	<p data-bbox="1486 277 1894 383">Preamble is not limiting, except for “insulating film on a substrate”</p>
<p data-bbox="201 537 606 748">“wherein an oxide material is deposited on the substrate, and the insulating film is formed by reactive sputtering in a mode between a metallic mode and a poison mode.”</p> <p data-bbox="201 789 548 854">U.S. Patent No. 7,381,657, Claim 2</p>	<p data-bbox="630 537 989 570">Plain and ordinary meaning</p>	<p data-bbox="1058 537 1465 781">“wherein an oxide material is deposited on the substrate and the insulating film comprising the oxide material is formed by reactive sputtering between a metallic mode and a poison mode”</p>	<p data-bbox="1486 537 1854 570">Plain-and-ordinary meaning</p>